

High Flux Reflectometry and Energy Analysis

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Motivation: Task 1

Increase Efficiency of Reflectometers:

- EASYREF: multilayer monochromators after sample
- REFOCUS: combine graded mono with elliptic shape

Challenges:

- diffuse scattering from multilayers
- increase reflectivity
- adjustment of beam divergence
- focusing
- length of substrates

Contributions TUM / FRM II

Hardware:

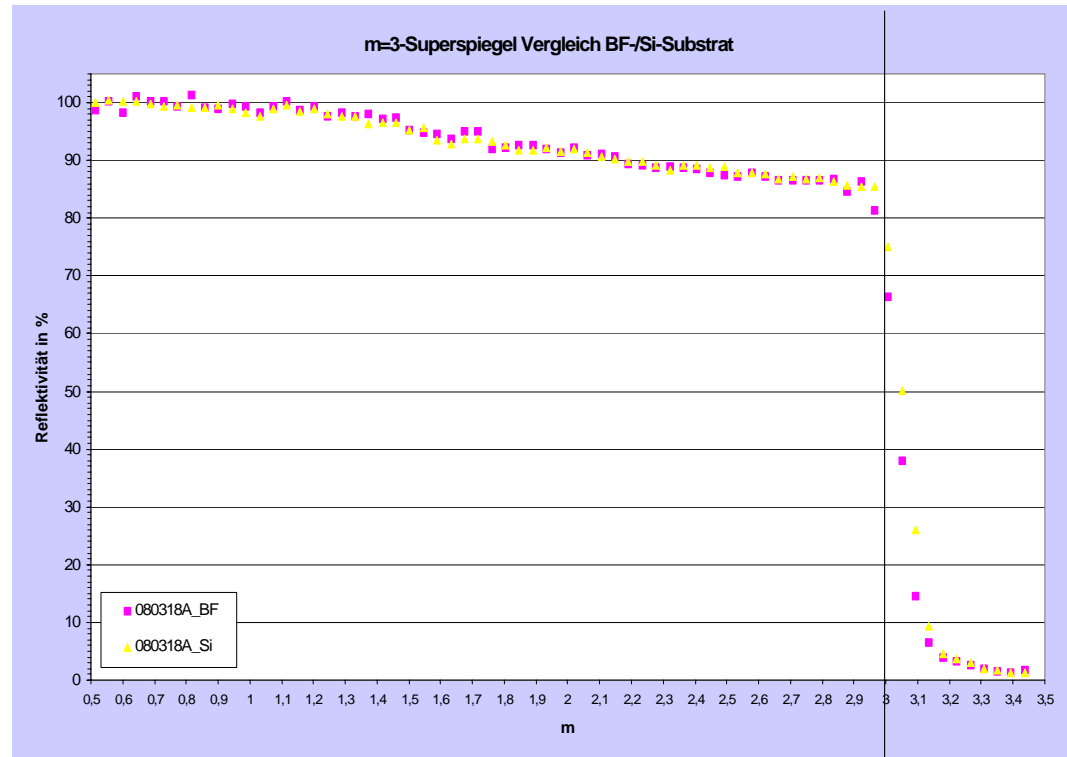
- Beamlines TREFF and MIRA:
 - specular, diffuse scattering
 - device characterization
- DC-magnetron sputtering plant:
 - length of substrates $L = 1\text{m}$



Contributions TUM – FRM II

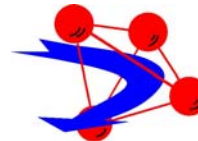
Hardware:

- Beamlines TREFF and MIRA:
 - specular, diffuse scattering
 - device characterization
- DC-magnetron sputtering plant:
 - length of substrates $L = 1$ m
 - $m > 3$
- Expertise in Monte-Carlo simulations:
 - McStas



Collaborations

Topics:	Collaboration with
• diffuse scattering / graded multilayers: <ul style="list-style-type: none">◦ increase $R \rightarrow$ bandpass monochromators◦ E-analysis \rightarrow graded bandpass (may replace velocity selector)	PSI
• adjustment of beam divergence: (see also adaptive optics)	PSI
• focusing:	PSI
• simulations:	UCPH
• design of devices:	LLB, ILL, PSI
• length of substrates:	LLB, PSI
• implementation (reflect., SANS, ..)	LLB, ILL, PSI



UCPH